

CLEANING CHEMICAL SUPPLYING DEVICE,  
CLEANING CHEMICAL SUPPLYING METHOD, AND CLEANING UNIT

ABSTRACT OF THE DISCLOSURE

A cleaning chemical supplying device, a cleaning chemical supplying method, and a cleaning unit capable of flexibly handling a change of a dilution ratio and suppression of an increase of a device size are provided.

A cleaning chemical supplying device has a first in-line mixer 72 for supplying a first cleaning chemical to a cleaning device 200, a second in-line mixer 73 for supplying a second cleaning chemical to the substrate cleaning device 200, a first chemical CLC box 120 for controlling a flow rate of the first chemical supplied to the first in-line mixer 72, a second chemical CLC box 130 for controlling a flow rate of the second chemical supplied to the second in-line mixer 73, and a DIWCLC box 110 for controlling a flow rate of dilution water supplied to the first in-line mixer 72 or the second in-line mixer 73 and is configured such that a supply destination of the dilution water is switched from the first in-line mixer 72 to the second in-line mixer 73 or from the second in-line mixer 73 to the first in-line mixer 72.

[Selected Drawing]

FIG. 2